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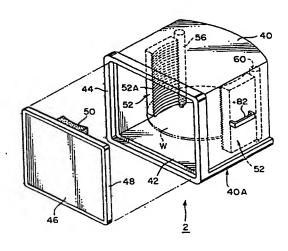
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(54) UNPROCESSED MATERIAL STORING DEVICE AND CARRY-IN/OUT STAGE

The present invention relates to a housing (57)apparatus for housing therein an object to be processed, such as a semiconductor wafer, in a space filled with an inert gas when the object is transferred between various process systems. This housing apparatus has a door 46, which is airtightly open and closed, and comprises a container body 40 for housing therein a semiconductor wafer W. The container body 40 is provided with an intake port for introducing an inert gas, and an exhaust port for exhausting an inside atmosphere. On the distal end part of an intake nozzle which is connected to the intake port and which extends into the container body 40, a diffusion-force suppressing member 56 for suppressing a diffusion force of an introduced inert gas is provided, On the distal end part of an exhaust nozzle which is connected to the exhaust port and which extends into the container body 40, a convergent-force suppressing member 60 for suppressing a convergent force of an exhausted gas is provided.



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